

**RESTRICTION REQUIREMENT**

The Examiner has required restriction between:

Group I: Claims 1-14, drawn to a method for etching a silicon substrate, classified in class 438, subclass 706; or

Group II: Claims 15-24, drawn to a device/apparatus for etching a silicon substrate, classified in class 156, subclass 345.48.

In response, Applicants provisionally elect Group II: claims 15-24 drawn to a device/apparatus for etching a silicon substrate, with traverse.

**CONCLUSION**

In view of the above remarks, withdrawal of this restriction requirement is respectfully requested.

An early examination is respectfully requested.

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Respectfully submitted,

By 

Louis J. DelJude

Registration No.: 47,522

DARBY & DARBY P.C.

P.O. Box 5257

New York, New York 10150-5257

(212) 527-7700

(212) 527-7701 (Fax)

Attorneys/Agents For Applicant